

	Type	L #	Hits	Search Text	DBs	Tim Stamp
1	BRS	L9	0	ryuji-biro.in.	USPAT	2003/08/19 12:30
2	BRS	L10	0	minoru-otani.in.	USPAT	2003/08/19 12:30
3	BRS	L11	0	kenji-ando.in.	USPAT	2003/08/19 12:31
4	BRS	L12	0	yasuyuki-suzuki.in.	USPAT	2003/08/19 12:32
5	BRS	L13	0	hidehiro-kanazawa.in.	USPAT	2003/08/19 12:32
6	BRS	L14	77626	optical and (clean\$3 or rins\$3)	USPAT	2003/08/19 12:34
7	BRS	L15	14332	14 and irradiat\$3	USPAT	2003/08/19 12:35
8	BRS	L16	2122	14 and (irradiat\$3 near5 ultraviolet)	USPAT	2003/08/19 12:36
9	BRS	L18	0	14 and (rins\$3 near5 gas)	USPAT	2003/08/19 12:51
10	BRS	L17	286	16 and (gas near5 (inert or inactive))	USPAT	2003/08/19 12:52

	Comments	Error Definition	Errors
1			0
2			0
3			0
4			0
5			0
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8			0
9			0
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	1	Document ID	Issue Date	Pages	Title
1	<input type="checkbox"/>	US 6605815 B2	20030812	12	Method of lithography using vacuum ultraviolet radiation
2	<input type="checkbox"/>	US 6603101 B2	20030805	30	Heating device, method for evaluating heating device and pattern forming method
3	<input type="checkbox"/>	US 6599790 B1	20030729	29	Laser-irradiation method and laser-irradiation device
4	<input type="checkbox"/>	US 6593288 B2	20030715	11	Use of an amphoteric polymer to treat a hard surface
5	<input type="checkbox"/>	US 6593034 B1	20030715	5	Framed pellicle for protection of photolithographic photomask
6	<input type="checkbox"/>	US 6586811 B2	20030701	34	Microlens, solid state imaging device, and production process thereof
7	<input type="checkbox"/>	US 6580094 B1	20030617	28	Electro luminescence display device
8	<input type="checkbox"/>	US 6576578 B1	20030610	6	Synthetic quartz glass and method for preparing the same
9	<input type="checkbox"/>	US 6576302 B1	20030610	10	Method for producing a metal oxide and method for forming a minute pattern
10	<input type="checkbox"/>	US 6572934 B2	20030603	33	Method for manufacturing a magnetic recording disk
11	<input type="checkbox"/>	US 6571057 B2	20030527	23	Optical instrument, gas replacement method and cleaning method of optical instrument, exposure apparatus, exposure method and manufacturing method for devices
12	<input type="checkbox"/>	US 6569261 B1	20030527	19	Cleaning composition comprising a water-soluble or water-dispersible polymer
13	<input type="checkbox"/>	US 6566278 B1	20030520	21	Method for densification of CVD carbon-doped silicon oxide films through UV irradiation

	Current OR	Current XRef	Retrieval Classif	Inventor	S
1	250/492.2	430/311; 430/325; 430/396		Gelernt, Barry	<input checked="" type="checkbox"/>
2	219/502	118/725; 219/497; 250/559.06; 374/120		Hayasaki, Kei et al.	<input type="checkbox"/>
3	438/166	438/308; 438/795; 438/798		Yamazaki, Shunpei et al.	<input type="checkbox"/>
4	510/504	134/42; 510/180; 510/181; 510/426; 510/427; 510/433; 510/476; 510/499; 510/503		Aubay, Eric et al.	<input type="checkbox"/>
5	430/5	355/75; 428/14		Shirasaki, Toru	<input type="checkbox"/>
6	257/432			Sekine, Yasuhiro	<input type="checkbox"/>
7	257/79	257/344; 257/379; 257/408		Yamazaki, Shunpei et al.	<input type="checkbox"/>
8	501/54	65/111; 65/17.4; 65/17.6		Ikuta, Yoshiaki et al.	<input type="checkbox"/>
9	427/597	427/492; 427/508; 427/554; 427/556; 427/595; 427/596		Mizuta, Susumu et al.	<input type="checkbox"/>
10	427/534	427/130; 427/131; 427/294; 427/350; 427/355; 427/385.5; 427/402; 427/407.1; 427/535; 427/536; 427/539; 427/555; 427/569; 427/596; 427/599; 428/65.4; 428/65.8		Watanabe, Naoki et al.	<input type="checkbox"/>
11	396/53	250/492.1; 355/67; 430/311		Aoki, Takashi	<input type="checkbox"/>
12	134/39	134/38; 134/40; 134/42; 510/229; 510/238; 510/240; 510/241; 510/243; 510/244; 510/475; 510/480; 510/504		Aubay, Eric et al.	<input type="checkbox"/>
13	438/778	427/553; 427/558; 438/788; 438/789; 438/790		Harvey, Keith R. et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
14	<input type="checkbox"/>	US 6566199 B2	20030520	28	Method and system for forming film, semiconductor device and fabrication method thereof
15	<input type="checkbox"/>	US 6565927 B1	20030520	39	Method for treatment of surfaces with ultraviolet light
16	<input type="checkbox"/>	US 6565763 B1	20030520	59	Method for manufacturing porous structure and method for forming pattern
17	<input type="checkbox"/>	US 6563565 B2	20030513	28	Apparatus and method for projection exposure
18	<input type="checkbox"/>	US 6544727 B1	20030408	146	Methods and devices for the removal of psoralens from blood products
19	<input type="checkbox"/>	US 6533633 B2	20030318	34	Methods of manufacturing aperture fluorescent lamp and surface illuminator
20	<input type="checkbox"/>	US 6528358 B1	20030304	123	Semiconductor device and method for fabricating the same
21	<input type="checkbox"/>	US 6524715 B1	20030225	32	Thin-film forming chemical adsorption material, producing method thereof and applications thereof
22	<input type="checkbox"/>	US 6524663 B1	20030225	8	Method for selective activation and metallization of materials
23	<input type="checkbox"/>	US 6522384 B2	20030218	17	Exposure method and apparatus, and device manufacturing method
24	<input type="checkbox"/>	US 6517403 B1	20030211	31	Visual display
25	<input type="checkbox"/>	US 6511617 B1	20030128	69	Consolidated contact lens molding

	Current OR	Current XRef	Retrieval Classif	Inventor	S
14	438/261	438/770; 438/773; 438/787		Tokai, Nobuo et al.	<input type="checkbox"/>
15	427/487	427/398.1; 427/457; 427/492; 427/556		Drzal, Lawrence T. et al.	<input type="checkbox"/>
16	216/56	216/22; 216/24; 216/40; 216/41; 216/67; 521/61		Asakawa, Koji et al.	<input type="checkbox"/>
17	355/53	355/67; 355/71		Nishi, Kenji	<input type="checkbox"/>
18	435/2	424/529; 424/530; 424/531; 435/173.1; 435/173.9; 604/262; 604/403; 604/406; 604/408; 604/409; 604/410; 604/5.01; 604/5.02; 604/6.08; 604/6.09; 604/6.1; 604/6.15		Hei, Derek J.	<input type="checkbox"/>
19	445/26	445/22		Ono, Shin-Ichirou	<input type="checkbox"/>
20	438/151	257/E21.133; 257/E21.192; 257/E21.318; 257/E21.413; 257/E21.703; 257/E27.111; 438/152; 438/161; 438/162		Yamazaki, Shunpei et al.	<input type="checkbox"/>
21	428/447	428/421; 556/436; 556/465; 556/466; 556/471; 556/484		Ootake, Tadashi et al.	<input type="checkbox"/>
22	427/553	427/125; 427/229; 427/259; 427/282; 427/304; 427/305; 427/437; 427/443.1; 427/98		Kelly, Patrick V. et al.	<input type="checkbox"/>
23	355/30	355/53; 355/67		Miwa, Yoshinori	<input type="checkbox"/>
24	445/25	445/41		Cooper, Anthony John et al.	<input type="checkbox"/>
25	264/1.36	264/102; 264/334; 425/150; 425/73; 425/808		Martin, Wallace Anthony et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
26	<input type="checkbox"/>	US 6509957 B1	20030121	37	Stage device and exposure apparatus
27	<input type="checkbox"/>	US 6506253 B2	20030114	13	Photo-excited gas processing apparatus for semiconductor process
28	<input type="checkbox"/>	US 6504174 B1	20030107	122	Semiconductor device and method for fabricating the same
29	<input type="checkbox"/>	US 6503632 B1	20030107	32	Polydialkylsiloxane/polyamide copolymer, process for producing the same, and various materials
30	<input type="checkbox"/>	US 6498428 B1	20021224	15	Organic electroluminescent element and method for manufacturing same
31	<input type="checkbox"/>	US 6497783 B1	20021224	47	Plasma processing apparatus provided with microwave applicator having annular waveguide and processing method
32	<input type="checkbox"/>	US 6494584 B1	20021217	28	Ultraviolet optical device having an optical part with a gas sprayed thereon
33	<input type="checkbox"/>	US 6493066 B1	20021210	13	Exposure apparatus
34	<input type="checkbox"/>	US 6488825 B1	20021203	23	Optically coupled sputter apparatus
35	<input type="checkbox"/>	US 6475881 B1	20021105	12	Fabrication process of a semiconductor device including a dicing process of a semiconductor wafer
36	<input type="checkbox"/>	US 6467491 B1	20021022	20	Processing apparatus and processing method
37	<input type="checkbox"/>	US 6462199 B1	20021008	58	Silver halide color photographic light-sensitive material, phenidone compound for use therein, and method of producing the same
38	<input type="checkbox"/>	US 6461437 B1	20021008	17	Apparatus used for fabricating liquid crystal device and method of fabricating the same
39	<input type="checkbox"/>	US 6458253 B2	20021001	28	Thin film production process and optical device
40	<input type="checkbox"/>	US 6456642 B1	20020924	16	Optical coupling device

	Curr nt OR	Current XRef	Retri val Classif	Inventor	S
26	355/72	250/492.2; 250/492.22; 355/53; 355/67; 355/74; 355/75; 355/77; 356/399; 356/400; 356/401		Tanaka, Keichi	<input type="checkbox"/>
27	118/620	118/715; 118/719		Sakuma, Takeshi	<input type="checkbox"/>
28	257/64	257/151; 257/59; 257/63; 257/65; 257/66; 257/E21.133; 257/E21.192; 257/E21.318; 257/E21.413; 257/E21.703; 257/E27.111; 438/150		Yamazaki, Shunpei et al.	<input type="checkbox"/>
29	428/447	428/474.4; 525/431		Hayashi, Akio et al.	<input type="checkbox"/>
30	313/506	257/E27.119; 257/E51.02; 313/483; 313/500		Matsuura, Masahide et al.	<input type="checkbox"/>
31		156/345.34; 156/345.41		Suzuki, Nobumasa et al.	<input type="checkbox"/>
32	359/507	359/509		Wada, Hiroyuki et al.	<input type="checkbox"/>
33	355/67			Miwa, Yoshinori	<input type="checkbox"/>
34	204/298.06	204/298.04; 204/298.08		Hilliard, Donald Bennett	<input type="checkbox"/>
35	438/464	257/E21.599; 29/25.01; 29/33M; 438/113; 438/458; 438/460; 438/977		Yamada, Yutaka	<input type="checkbox"/>
36	134/1.3	134/32; 134/902; 156/345.32; 156/345.5		Sugiura, Masahito et al.	<input type="checkbox"/>
37	548/366.1			Mikoshiba, Hisashi et al.	<input type="checkbox"/>
38	118/719	118/715; 156/345.11; 156/345.21; 156/345.22; 156/345.31; 156/345.32; 156/345.5; 156/345.55; 414/217.1; 414/935; 414/937; 414/939; 414/940		Kubota, Takeshi et al.	<input type="checkbox"/>
39	204/192.15	204/192.12; 204/192.26		Ando, Kenji et al.	<input type="checkbox"/>
40	372/55	250/493.1; 372/43; 372/57		Hilliard, Donald Bennett	<input type="checkbox"/>

	1	Document ID	Issue Dat	Pages	Title
41	<input type="checkbox"/>	US 6455359 B1	20020924	28	Laser-irradiation method and laser-irradiation device
42	<input type="checkbox"/>	US 6451392 B1	20020917	41	Chemical adsorbate compound, organic film, liquid crystal alignment film, and liquid crystal display device utilizing the chemical adsorbate compound
43	<input type="checkbox"/>	US 6448492 B1	20020910	23	Transparent member for shielding electromagnetic waves and method of producing the same
44	<input type="checkbox"/>	US 6441351 B2	20020827	30	Heating device, method for evaluating heating device and pattern forming method
45	<input type="checkbox"/>	US 6436542 B1	20020820	11	Multilayer structure and process for producing the same
46	<input type="checkbox"/>	US 6433102 B1	20020813	26	Hydrogenated polymers, resin composition, and process for producing substrate for information-recording medium
47	<input type="checkbox"/>	US 6432790 B1	20020813	39	Method of manufacturing photomask, photomask, and method of manufacturing semiconductor integrated circuit device
48	<input type="checkbox"/>	US 6428884 B1	20020806	15	Magnetic recording medium
49	<input type="checkbox"/>	US 6420003 B2	20020716	11	Acrylate composite barrier coating
50	<input type="checkbox"/>	US 6414743 B1	20020702	73	Exposure apparatus, exposure method using the same and method of manufacture of circuit device
51	<input type="checkbox"/>	US 6413805 B1	20020702	24	Semiconductor device forming method
52	<input type="checkbox"/>	US 6406782 B2	20020618	25	Sealant composition, article including same, and method of using same

	Current OR	Current XR f	Retri val Classif	Inventor	S
41	438/166	257/E21.703; 257/E27.111; 438/308; 438/795; 438/798		Yamazaki, Shunpei et al.	<input type="checkbox"/>
42	428/1.23	252/299.4; 427/387; 427/510; 427/515		Ootake, Tadashi et al.	<input type="checkbox"/>
43	174/35MS	174/35R; 348/819; 348/820		Okada, Atsushi et al.	<input type="checkbox"/>
44	219/502	219/497; 250/559.27; 374/121; 392/416		Hayasaki, Kei et al.	<input type="checkbox"/>
45	428/432	428/426; 428/428; 428/448; 428/697; 428/702		Ogino, Etsuo et al.	<input type="checkbox"/>
46	525/333.3	525/332.9; 525/338; 525/339		Suzuki, Teruhiko et al.	<input type="checkbox"/>
47	438/377	438/669		Okamoto, Yoshihiko et al.	<input type="checkbox"/>
48	428/323	428/336; 428/402; 428/425.9; 428/694BA; 428/694BN; 428/694BS		Naoe, Koji et al.	<input type="checkbox"/>
49	428/35.9	428/215; 428/216; 428/336; 428/35.3; 428/35.8; 428/451; 428/463; 428/475.8; 428/476.3; 428/483; 428/520; 428/522		Shaw, David G. et al.	<input type="checkbox"/>
50	355/69	355/30; 355/53		Nishi, Kenji et al.	<input type="checkbox"/>
51	438/166	257/E21.133; 257/E21.413; 257/E21.703; 438/164; 438/487		Zhang, Hongyong et al.	<input type="checkbox"/>
52	428/317.7	156/278; 156/280; 156/307.5; 156/309.6; 156/312; 156/313; 156/324.4; 427/208.2; 427/400; 428/308.8; 428/314.4; 428/317.1; 428/319.3; 428/426; 428/430; 428/457; 428/458		Johnson, Michael A. et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
53	<input type="checkbox"/>	US 6401317 B1	20020611	11	Apparatus for fabricating a semiconductor device
54	<input type="checkbox"/>	US 6399158 B1	20020604	15	Method and apparatus for curing ultraviolet-curing resin
55	<input type="checkbox"/>	US 6396023 B1	20020528	11	Airtight sealing method and airtight sealing apparatus for semiconductor laser element
56	<input type="checkbox"/>	US 6391522 B1	20020521	31	Offset printing plate precursor and method for offset printing using the same
57	<input type="checkbox"/>	US 6391117 B1	20020521	7	Method of washing substrate with UV radiation and ultrasonic cleaning
58	<input type="checkbox"/>	US 6387602 B1	20020514	8	Apparatus and method of cleaning reticles for use in a lithography tool
59	<input type="checkbox"/>	US 6385290 B1	20020507	18	X-ray apparatus
60	<input type="checkbox"/>	US 6384427 B1	20020507	28	Electronic device
61	<input type="checkbox"/>	US 6376401 B1	20020423	18	Ultraviolet ray-transparent optical glass material and method of producing same
62	<input type="checkbox"/>	US 6372827 B1	20020416	25	Sealant composition, article including same, and method of using same
63	<input type="checkbox"/>	US 6369398 B1	20020409	12	Method of lithography using vacuum ultraviolet radiation

	Current OR	Current XRef	Retrieval Classif	Inventor	S
53	29/33M	250/492.2; 257/E21.599; 29/25.01; 438/113; 438/458; 438/460; 438/464		Yamada, Yutaka	<input type="checkbox"/>
54	427/513	118/622; 118/642; 250/492.1; 427/163.2; 427/487; 427/508; 427/553; 427/558		Kuwahara, Kazuya et al.	<input type="checkbox"/>
55	219/117.1	134/1; 134/1.3; 134/26; 134/39; 134/40; 219/105; 219/107; 219/81; 219/82; 219/83; 219/84; 219/86.9; 257/432; 257/433; 257/81; 257/82; 257/83; 257/84; 372/6; 438/706; 438/707; 438/708; 438/709		Aikiyo, Takeshi	<input type="checkbox"/>
56	430/273.1	430/19; 430/306; 430/944; 430/945		Nakayama, Takao et al.	<input type="checkbox"/>
57	134/1	134/1.3; 134/2; 134/26; 134/30; 134/902		Suzuki, Masaaki	<input type="checkbox"/>
58	430/327	134/1; 134/122P; 134/133; 134/18; 134/39; 134/64P; 216/12; 355/99; 430/5		Hayden, Cindy J. et al.	<input type="checkbox"/>
59	378/84			Kondo, Hiroyuki et al.	<input type="checkbox"/>
60	257/59	257/72; 257/E21.703; 257/E27.111		Yamazaki, Shunpei et al.	<input type="checkbox"/>
61	501/54	65/17.4; 65/414; 65/421		Kondo, Shinichi et al.	<input type="checkbox"/>
62	523/467	156/278; 156/280; 156/307.5; 156/309.6; 156/312; 156/313; 156/324.4; 524/558		Johnson, Michael A. et al.	<input type="checkbox"/>
63	250/492.2	430/311; 430/325; 430/396		Gelernt, Barry	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
64	<input type="checkbox"/>	US 6366015 B1	20020402	41	Method of manufacturing electron-emitting device, electron source and image-forming apparatus using the same
65	<input type="checkbox"/>	US 6365933 B1	20020402	30	Semiconductor device and method of manufacturing the same
66	<input type="checkbox"/>	US 6358316 B1	20020319	56	Method for producing semiconductor device, method for producing semiconductor laser device, and method for producing quantum wire structure
67	<input type="checkbox"/>	US 6351068 B1	20020226	19	Transparent conductive laminate and electroluminescence light-emitting element using same
68	<input type="checkbox"/>	US 6348369 B1	20020219	18	Method for manufacturing semiconductor devices
69	<input type="checkbox"/>	US 6340824 B1	20020122	125	Semiconductor light emitting device including a fluorescent material
70	<input type="checkbox"/>	US 6334803 B1	20020101	44	Method of manufacturing electron-emitting device, electron source and image-forming apparatus using the same
71	<input type="checkbox"/>	US 6319634 B1	20011120	41	Projection lithography photomasks and methods of making
72	<input type="checkbox"/>	US 6319404 B1	20011120	17	Process for the preparation of porous material and porous material
73	<input type="checkbox"/>	US 6319321 B1	20011120	22	Thin-film fabrication method and apparatus
74	<input type="checkbox"/>	US 6317274 B1	20011113	12	Optical element
75	<input type="checkbox"/>	US 6288769 B1	20010911	17	Optical device method of cleaning the same, projection aligner, and method of producing the same
76	<input type="checkbox"/>	US 6284360 B1	20010904	26	Sealant composition, article including same, and method of using same
77	<input type="checkbox"/>	US 6278516 B1	20010821	20	Projection exposure apparatus and method of producing a device using a projection exposure apparatus

	Current OR	Current XRef	Retrieval Classif	Invent r	S
64	313/495	313/309; 313/336; 313/351; 313/497		Shibata, Masaaki	<input type="checkbox"/>
65	257/347	257/E21.703; 257/E27.111		Yamazaki, Shunpei et al.	<input type="checkbox"/>
66	117/105	117/89; 117/954; 257/E21.09; 257/E21.131; 257/E21.222; 257/E21.232; 257/E21.266; 257/E21.408; 438/29; 438/39; 438/40; 438/41; 438/761		Kizuki, Hirotaka et al.	<input type="checkbox"/>
67	313/506	428/917		Yamazaki, Fumiharu et al.	<input type="checkbox"/>
68	438/166	117/8; 134/1; 257/E21.134; 257/E21.413; 438/906		Kusumoto, Naoto et al.	<input type="checkbox"/>
69	257/99	257/100; 257/89; 257/98; 257/E33.061; 313/512		Komoto, Satoshi et al.	<input type="checkbox"/>
70	445/51	427/78; 445/6		Shibata, Masaaki	<input type="checkbox"/>
71	430/5	428/426; 65/397		Berkey, George Edward et al.	<input type="checkbox"/>
72	210/500.29	210/500.27; 210/500.34; 210/500.35; 210/500.38; 210/500.39; 210/500.41; 210/500.42; 264/41; 264/425; 264/48; 264/49; 428/315.7		Zhang, Husheng et al.	<input type="checkbox"/>
73	118/666	118/50.1; 118/641; 118/725; 427/372.2; 427/521; 427/553; 427/557		Hiraga, Takashi et al.	<input type="checkbox"/>
74	359/742	359/355; 359/509; 359/565; 359/566		Kato, Hideo et al.	<input type="checkbox"/>
75	355/30	355/53; 355/77		Akagawa, Masayuki et al.	<input type="checkbox"/>
76	428/317.7	428/308.8; 428/314.4; 428/317.1; 428/319.3; 428/426; 428/430; 428/457; 428/458		Johnson, Michael A. et al.	<input type="checkbox"/>
77	355/67	355/53; 355/73		Miwa, Yoshinori et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
78	<input type="checkbox"/>	US 6270723 B1	20010807	11	Rapid cryobaric sterilization and vaccine preparation
79	<input type="checkbox"/>	US 6268904 B1	20010731	44	Optical exposure apparatus and photo-cleaning method
80	<input type="checkbox"/>	US 6268071 B1	20010731	12	Organic electroluminescent device
81	<input type="checkbox"/>	US 6261881 B1	20010717	34	Semiconductor device provided with semiconductor circuit consisting of semiconductor element and method of manufacturing the same
82	<input type="checkbox"/>	US 6259509 B1	20010710	16	Exposure apparatus and device manufacturing method
83	<input type="checkbox"/>	US 6259204 B1	20010710	12	Organic electroluminescent device
84	<input type="checkbox"/>	US 6258521 B1	20010710	60	Silver halide color photographic light-sensitive material, phenidone compound for use therein, and method of producing the same
85	<input type="checkbox"/>	US 6252261 B1	20010626	34	GaN crystal film, a group III element nitride semiconductor wafer and a manufacturing process therefor
86	<input type="checkbox"/>	US 6251232 B1	20010626	29	Method of removing accumulated films from the surface of substrate holders in film deposition apparatus, and film deposition apparatus
87	<input type="checkbox"/>	US 6246070 B1	20010612	30	Semiconductor device provided with semiconductor circuit made of semiconductor element and method of fabricating the same
88	<input type="checkbox"/>	US 6231939 B1	20010515	11	Acrylate composite barrier coating

	Current OR	Current XRef	Retrieval Classif	Inventor	S
78	422/39	422/1; 435/236; 436/543		Laugharn, Jr., James A. et al.	<input type="checkbox"/>
79	355/53	250/492.2; 355/67; 355/68; 355/69; 355/71; 430/30		Mori, Takashi et al.	<input type="checkbox"/>
80	428/690	257/100; 257/99; 257/E51.02; 313/504; 313/506; 313/512; 428/913; 428/917		Yasukawa, Kouji et al.	<input type="checkbox"/>
81	438/161	257/69; 438/149		Yamazaki, Shunpei et al.	<input type="checkbox"/>
82	355/53			Miwa, Yoshinori et al.	<input type="checkbox"/>
83	313/512	257/E51.02; 313/493; 313/504; 313/506		Ebisawa, Akira et al.	<input type="checkbox"/>
84	430/551	430/543; 430/546; 430/607		Mikoshiba, Hisashi et al.	<input type="checkbox"/>
85	257/190	257/615; 257/76		Usui, Akira et al.	<input type="checkbox"/>
86	204/192.32	118/503; 118/620; 134/1; 134/1.1; 134/66; 204/298.25; 204/298.26; 204/298.31; 204/298.35; 216/37; 216/63; 216/66		Aruga, Yoshiki et al.	<input type="checkbox"/>
87	257/40	257/347; 257/49; 257/59; 257/635; 257/642; 257/643; 257/84; 257/E21.703; 257/E27.111; 438/149; 438/166; 438/587; 438/703; 438/763; 438/780		Yamazaki, Shunpei et al.	<input type="checkbox"/>
88	428/35.9	428/213; 428/215; 428/216; 428/336; 428/35.3; 428/35.8; 428/451; 428/463; 428/475.8; 428/476.3; 428/483; 428/520		Shaw, David G. et al.	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pages	Titl
89	<input type="checkbox"/>	US 6228751 B1	20010508	22	Method of manufacturing a semiconductor device
90	<input type="checkbox"/>	US 6225205 B1	20010501	20	Method of forming bump electrodes
91	<input type="checkbox"/>	US 6219113 B1	20010417	289	Method and apparatus for driving an active matrix display panel
92	<input type="checkbox"/>	US 6201260 B1	20010313	10	Thin film transistor and method of manufacturing the same
93	<input type="checkbox"/>	US 6191397 B1	20010220	31	Heating device, method for evaluating heating device and pattern forming method
94	<input type="checkbox"/>	US 6188179 B1	20010213	11	Induction circuits for lighting
95	<input type="checkbox"/>	US 6175186 B1	20010116	16	Organic electroluminescent element and method for manufacturing the same
96	<input type="checkbox"/>	US 6165256 A	20001226	20	Photocatalytically hydrophilifiable coating composition
97	<input type="checkbox"/>	US 6164295 A	20001226	18	CVD apparatus with high throughput and cleaning method therefor
98	<input type="checkbox"/>	US 6140165 A	20001031	23	Semiconductor device forming method
99	<input type="checkbox"/>	US 6114805 A	20000905	12	Organic electroluminescent display with filter layer
100	<input type="checkbox"/>	US 6110531 A	20000829	24	Method and apparatus for preparing integrated circuit thin films by chemical vapor deposition
101	<input type="checkbox"/>	US 6104530 A	20000815	27	Transparent laminates and optical filters for displays using same

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89	438/585	134/1.2; 438/149; 438/151; 438/758; 438/774; 438/974		Yamazaki, Shunpei et al.	<input type="checkbox"/>
90	438/613	257/E21.508; 257/E23.021; 438/616		Kinoshita, Makoto	<input type="checkbox"/>
91	349/42	345/98; 349/43; 349/45		Takahara, Hiroshi	<input type="checkbox"/>
92	257/66	257/655; 257/E21.413; 257/E29.28; 257/E29.299		Suzuki, Mitsuaki et al.	<input type="checkbox"/>
93	219/497	118/725; 219/405; 430/330		Hayasaki, Kei et al.	<input type="checkbox"/>
94	315/244	315/242; 315/243; 363/24		Boys, John Talbot et al.	<input type="checkbox"/>
95	313/483	257/E27.119; 257/E51.02; 313/500		Matsuura, Masahide et al.	<input type="checkbox"/>
96	106/13	106/286.1; 106/286.3; 106/286.4; 106/287.1; 106/287.13; 106/287.14; 106/287.16; 106/287.18; 106/287.19; 106/287.34		Hayakawa, Makoto et al.	<input type="checkbox"/>
97	134/1.1	216/59; 216/60; 216/80		Ui, Akio et al.	<input type="checkbox"/>
98	438/166	257/E21.133; 257/E21.413; 438/164; 438/486		Zhang, Hongyong et al.	<input type="checkbox"/>
99	313/509	257/E51.02; 313/112; 313/504		Codama, Mitsufumi et al.	<input type="checkbox"/>
100	427/255.25	257/E21.01; 257/E21.011; 257/E21.272; 257/E27.085; 257/E27.104; 427/255.19; 427/255.32; 427/255.36; 438/758; 438/778; 438/785		Paz de Araujo, Carlos A. et al.	<input type="checkbox"/>
101	359/359	359/350; 359/360; 359/585; 359/588; 359/589; 428/336		Okamura, Tomoyuki et al.	<input type="checkbox"/>

	1	Document ID	Issu Date	Pages	Title
102	<input type="checkbox"/>	US 6093243 A	20000725	154	Semiconductor device and its fabricating method
103	<input type="checkbox"/>	US 6083598 A	20000704	21	Information recording medium, method for manufacturing the medium, and apparatus for manufacturing the medium
104	<input type="checkbox"/>	US 6080281 A	20000627	14	Scrubbing of contaminants from contaminated air streams with aerogel materials with optional photocatalytic destruction
105	<input type="checkbox"/>	US 6077731 A	20000620	120	Semiconductor device and method for fabricating the same
106	<input type="checkbox"/>	US 6071440 A	20000606	41	Contact lens production line pallet system
107	<input type="checkbox"/>	US 6066872 A	20000523	153	Semiconductor device and its fabricating method
108	<input type="checkbox"/>	US 6058940 A	20000509	19	Method and system for assay and removal of harmful toxins during processing of tobacco products
109	<input type="checkbox"/>	US 6048588 A	20000411	30	Method for enhancing chemisorption of material

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102	117/8	117/9; 257/E21.012; 257/E21.133; 257/E21.197; 257/E21.352; 257/E21.396; 257/E21.413; 257/E21.414; 257/E21.426; 257/E21.43; 257/E29.293; 257/E29.294; 438/250; 438/251; 438/253; 438/255; 438/381; 438/393; 438/395; 438/399		Okada, Takako et al.	<input type="checkbox"/>
103	428/64.1	369/283; 369/288; 428/457; 428/64.4; 428/64.5; 428/64.7; 428/65.2; 428/913; 430/270.12; 430/495.1; 430/945		Ohkubo, Yoshiyuki et al.	<input type="checkbox"/>
104	204/157.3	423/210; 423/239.1; 423/245.3; 95/129; 95/90		Attia, Yosry A.	<input type="checkbox"/>
105	438/150	257/E21.133; 257/E21.703; 257/E27.111; 438/166; 438/487		Yamazaki, Shunpei et al.	<input type="checkbox"/>
106	264/1.1	264/102; 425/173; 425/808		Wang, Daniel Tsu-Fang et al.	<input type="checkbox"/>
107	257/309	257/534; 257/E21.012; 257/E21.133; 257/E21.197; 257/E21.352; 257/E21.396; 257/E21.413; 257/E21.414; 257/E21.426; 257/E21.43; 257/E29.293; 257/E29.294		Okada, Takako et al.	<input type="checkbox"/>
108	131/298	131/297; 131/300; 131/309; 131/310		Lane, Kerry Scott	<input type="checkbox"/>
109	427/554	134/1; 204/192.32; 216/65; 216/66; 219/121.69; 219/121.84; 257/E21.295; 257/E21.58; 427/596		Engelsberg, Audrey C.	<input type="checkbox"/>

	1	Document ID	Issu Date	Pages	Title
110	<input type="checkbox"/>	US 6039899 A	20000321	68	Consolidated contact lens molding
111	<input type="checkbox"/>	US 6028315 A	20000222	13	Cleaning apparatus
112	<input type="checkbox"/>	US 6027960 A	20000222	21	Laser annealing method and laser annealing device
113	<input type="checkbox"/>	US 6025115 A	20000215	68	Processing method for etching a substrate
114	<input type="checkbox"/>	US 6013418 A	20000111	10	Method for developing images in energy sensitive materials
115	<input type="checkbox"/>	US 6013335 A	20000111	42	Liquid crystal display apparatus and method for processing the same
116	<input type="checkbox"/>	US 6001431 A	19991214	16	Process for fabricating a magnetic recording medium
117	<input type="checkbox"/>	US 5981361 A	19991109	11	Fabrication process of a semiconductor device including a dicing process of a semiconductor wafer
118	<input type="checkbox"/>	US 5981001 A	19991109	65	Processing method for selectively irradiating a surface in presence of a reactive gas to cause etching
119	<input type="checkbox"/>	US 5965172 A	19991012	42	Contact lens production line pallet system
120	<input type="checkbox"/>	US 5964954 A	19991012	35	Double-sided substrate cleaning apparatus and cleaning method using the same

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110	264/1.36	118/256; 264/1.37; 264/1.38; 264/101; 264/102; 264/334; 425/135; 425/174.4; 425/347; 425/73; 425/808		Martin, Wallace Anthony et al.	<input type="checkbox"/>
111	250/455.11	250/454.11		Bailey, William et al.	<input type="checkbox"/>
112	438/166	257/E21.134; 257/E21.413; 438/662; 438/795		Kusumoto, Naoto et al.	<input type="checkbox"/>
113	430/313	257/E21.033; 257/E21.035; 257/E21.038; 257/E21.17; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.258; 257/E21.285; 257/E21.29; 257/E21.314; 430/330; 430/396		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
114	430/323	216/62; 430/325		Ma, Yi et al.	<input type="checkbox"/>
115	427/553	349/102; 349/167; 349/73; 349/77; 427/164; 427/555		Hirata, Mitsuaki et al.	<input type="checkbox"/>
116	427/569	427/128; 427/131; 427/249.7; 427/255.5; 427/255.7; 427/577; 427/906		Itoh, Kenji et al.	<input type="checkbox"/>
117	438/464	257/E21.599; 438/113; 438/458; 438/460; 438/977		Yamada, Yutaka	<input type="checkbox"/>
118	427/582	216/65; 216/66; 257/E21.033; 257/E21.035; 257/E21.038; 257/E21.17; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.258; 257/E21.285; 257/E21.29; 257/E21.314; 427/555; 427/557		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
119	425/186	425/453; 425/808		Wang, Daniel Tsu-Fang et al.	<input type="checkbox"/>
120	134/6	134/18; 134/26; 134/32; 134/902; 15/77		Matsukawa, Hiroyuki et al.	<input type="checkbox"/>

	1	Docum nt ID	Issue Date	Pages	Title
121	<input type="checkbox"/>	US 5962194 A	19991005	66	Processing method and apparatus
122	<input type="checkbox"/>	US 5958268 A	19990928	31	Removal of material by polarized radiation
123	<input type="checkbox"/>	US 5952429 A	19990914	55	Carbon black graft polymer, method for production thereof, and use thereof
124	<input type="checkbox"/>	US 5921744 A	19990713	33	Wafer carrying device and wafer carrying method
125	<input type="checkbox"/>	US 5914381 A	19990622	16	Degradable polymer and preparation process of the same
126	<input type="checkbox"/>	US 5906429 A	19990525	26	Optical illumination device
127	<input type="checkbox"/>	US 5889073 A	19990330	15	Process for producing material with hydrophilic surface
128	<input type="checkbox"/>	US 5882938 A	19990316	23	Apparatus and method for evaluating contamination caused by organic substances deposited on substrate surface
129	<input type="checkbox"/>	US 5879447 A	19990309	152	Semiconductor device and its fabricating method
130	<input type="checkbox"/>	US 5877843 A	19990302	25	Exposure apparatus

	Current OR	Current XRef	Retri val Classif	Inventor	S
121	430/312	257/E21.033; 257/E21.035; 257/E21.038; 257/E21.17; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.258; 257/E21.285; 257/E21.29; 257/E21.314; 430/317; 430/318; 430/394		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
122	219/121.84	134/1; 219/121.85; 257/E21.295; 257/E21.58		Engelsberg, Audrey C. et al.	<input type="checkbox"/>
123	525/326.1	428/402.24; 428/407; 525/327.3; 525/327.4; 525/329.7		Ikeda, Hayato et al.	<input type="checkbox"/>
124	414/755	414/935		Toda, Masayuki et al.	<input type="checkbox"/>
125	527/300	525/54.2; 525/54.21; 525/54.24; 525/54.3; 525/54.31; 527/311; 527/315		Terado, Yuji et al.	<input type="checkbox"/>
126	362/293	250/492.2; 362/264; 362/294; 362/345; 362/96; 95/137; 95/141; 96/142		Mori, Takashi et al.	<input type="checkbox"/>
127	522/3	522/6; 522/79; 522/84; 522/88; 522/89; 524/831; 524/845; 525/54.2; 525/54.3; 527/313; 527/314		Zhang, Husheng et al.	<input type="checkbox"/>
128	436/151	134/1; 134/2; 422/62; 422/82.02; 422/98; 436/149		Takahashi, Hideto et al.	<input type="checkbox"/>
129	117/8	117/9; 117/930; 257/E21.012; 257/E21.133; 257/E21.197; 257/E21.352; 257/E21.396; 257/E21.413; 257/E21.414; 257/E21.426; 257/E21.428; 257/E21.43; 257/E29.293; 257/E29.294		Okada, Takako et al.	<input type="checkbox"/>
130	355/30	355/53; 355/55		Takagi, Shin-ichi et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
131	<input type="checkbox"/>	US 5863706 A	19990126	63	Processing method for patterning a film
132	<input type="checkbox"/>	US 5858541 A	19990112	43	Glass composite material, precursor thereof, nitrogen-containing composite material and optical device
133	<input type="checkbox"/>	US 5858498 A	19990112	23	Information recording medium for manufacturing the medium, and apparatus for manufacturing the medium
134	<input type="checkbox"/>	US 5824456 A	19981020	9	Composition for forming metal oxide thin film pattern and method for forming metal oxide thin film pattern
135	<input type="checkbox"/>	US 5824455 A	19981020	73	Processing method and apparatus
136	<input type="checkbox"/>	US 5821175 A	19981013	44	Removal of surface contaminants by irradiation using various methods to achieve desired inert gas flow over treated surface
137	<input type="checkbox"/>	US 5807750 A	19980915	19	Optical substance analyzer and data processor

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131	430/313	216/51; 216/62; 216/74; 257/E21.033; 257/E21.035; 257/E21.038; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.285; 257/E21.29; 257/E21.314; 430/323; 430/394; 438/706; 438/724		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
132	428/429	525/420; 525/437; 528/34; 528/41; 528/43; 528/9		Hiraoka, Toshiro et al.	<input type="checkbox"/>
133	428/64.1	369/275.4; 369/283; 369/288; 428/457; 428/64.2; 428/64.4; 428/64.7; 428/65.2; 428/913; 430/270.12; 430/495.1; 430/945		Ohkubo, Yoshiyuki et al.	<input type="checkbox"/>
134	430/325	430/198; 430/270.1; 430/330; 430/919; 430/921		Ogi, Katsumi et al.	<input type="checkbox"/>
135	430/323	216/51; 257/E21.033; 257/E21.035; 257/E21.038; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.258; 257/E21.285; 257/E21.29; 257/E21.313; 257/E21.314; 430/313; 438/710		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
136	438/795	134/1; 134/1.3; 257/E21.226; 257/E21.295; 257/E21.3; 257/E21.304; 257/E21.58; 438/906		Engelsberg, Audrey C.	<input type="checkbox"/>
137	436/164	250/341.1; 356/436; 422/82.05; 422/82.09; 422/82.11; 422/83; 436/171		Baum, Marc M. et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
138	<input type="checkbox"/>	US 5804107 A	19980908	69	Consolidated contact lens molding
139	<input type="checkbox"/>	US 5797997 A	19980825	24	Oxygen producing thermophotovoltaic systems
140	<input type="checkbox"/>	US 5786367 A	19980728	35	Cyclic amide derivatives
141	<input type="checkbox"/>	US 5744357 A	19980428	42	Contact lens production line pallet system
142	<input type="checkbox"/>	US 5730922 A	19980324	23	Resin transfer molding process for composites
143	<input type="checkbox"/>	US 5725909 A	19980310	10	Acrylate composite barrier coating process
144	<input type="checkbox"/>	US 5725677 A	19980310	21	Dry cleaning process for cleaning a surface
145	<input type="checkbox"/>	US 5724187 A	19980303	53	Electrochromic mirrors and devices
146	<input type="checkbox"/>	US 5717051 A	19980210	43	Glass composite material, precursor thereof, nitrogen-containing composite material and optical device
147	<input type="checkbox"/>	US 5714306 A	19980203	68	Processing method and apparatus
148	<input type="checkbox"/>	US 5705329 A	19980106	21	Silver halide photographic light-sensitive material

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138	264/1.36	264/1.37; 264/102; 264/334; 425/135; 425/174.4; 425/347; 425/451.9; 425/73; 425/808; 425/90		Martin, Wallace Anthony et al.	<input type="checkbox"/>
139	136/253	204/252; 204/265; 204/266; 205/634		Noreen, Darryl L.	<input type="checkbox"/>
140	514/312	546/153; 546/157; 546/158		Oshiro, Yasuo et al.	<input type="checkbox"/>
141	425/347	264/1.1; 264/1.32; 425/107; 425/135; 425/259; 425/261; 425/404; 425/446; 425/453; 425/454; 425/73; 425/808; 425/DIG.108; 425/DIG.201		Wang, Daniel Tsu-Fang et al.	<input type="checkbox"/>
142	264/258	264/257		Babb, David A. et al.	<input type="checkbox"/>
143	427/412.1	427/223; 427/255.6; 427/296; 427/316; 427/404; 427/419.5; 427/536		Shaw, David G. et al.	<input type="checkbox"/>
144	134/1	134/2; 134/21; 134/3; 257/E21.226; 257/E21.252		Sugino, Rinji et al.	<input type="checkbox"/>
145	359/608	359/265; 359/273; 359/603; 359/604		Varaprasad, Desaraju V. et al.	<input type="checkbox"/>
146	528/9	428/429; 525/420; 525/437; 528/34; 528/41; 528/43		Hiraoka, Toshiro et al.	<input type="checkbox"/>
147	430/323	216/41; 216/62; 257/E21.033; 257/E21.035; 257/E21.038; 257/E21.171; 257/E21.235; 257/E21.252; 257/E21.257; 257/E21.258; 257/E21.285; 257/E21.29; 257/E21.314; 430/324; 430/330		Komatsu, Toshiyuki et al.	<input type="checkbox"/>
148	430/536	430/523; 430/527; 430/531		Nakajima, Akihisa et al.	<input type="checkbox"/>

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149	<input type="checkbox"/>	US 5705328 A	19980106	23	Silver halide photographic light-sensitive material
150	<input type="checkbox"/>	US 5686143 A	19971111	33	Resist treating method
151	<input type="checkbox"/>	US 5666178 A	19970909	41	Liquid crystal display apparatus having plural regions of different aligning conditions and method for producing the same
152	<input type="checkbox"/>	US 5643472 A	19970701	24	Selective removal of material by irradiation
153	<input type="checkbox"/>	US 5637440 A	19970610	9	Composition for forming metal oxide thin film pattern and method for forming metal oxide thin film pattern
154	<input type="checkbox"/>	US 5630872 A	19970520	33	Formation of thin-film patterns of a metal oxide
155	<input type="checkbox"/>	US 5622872 A	19970422	21	Analyte detection through observed optical modulation of polymerized lipid layers
156	<input type="checkbox"/>	US 5622634 A	19970422	48	Method of manufacturing electron-emitting device, electron source and image-forming apparatus
157	<input type="checkbox"/>	US 5582640 A	19961210	154	Semiconductor device and its fabricating method
158	<input type="checkbox"/>	US 5578133 A	19961126	21	Dry cleaning process for cleaning a surface
159	<input type="checkbox"/>	US 5571568 A	19961105	19	Multilayered bioelectronic sensors
160	<input type="checkbox"/>	US 5545367 A	19960813	28	Rapid prototype three dimensional stereolithography

	Current OR	Current XRef	Retrieval Classif	Invent r	S
149	430/531	430/502; 430/523; 430/539		Shiozaki, Shigeru	<input type="checkbox"/>
150	427/271	257/E21.252; 427/384		Matsukawa, Hiroyuki et al.	<input type="checkbox"/>
151	349/136	349/129		Hirata, Mitsuaki et al.	<input type="checkbox"/>
152	216/65	134/1; 204/192.32; 216/66; 219/121.69; 219/121.84; 257/E21.226; 257/E21.295; 257/E21.3; 257/E21.304; 257/E21.58		Engelsberg, Audrey C. et al.	<input type="checkbox"/>
153	430/270.1	430/919; 430/921		Ogi, Katsumi et al.	<input type="checkbox"/>
154	106/287.18	106/287.19; 106/287.25; 257/E21.271; 257/E21.272		Ogi, Katsumi et al.	<input type="checkbox"/>
155	436/518	204/403.01; 204/403.08; 422/82.08; 422/82.09; 435/288.7; 435/7.1; 435/7.5; 436/532		Ribi, Hans O.	<input type="checkbox"/>
156	216/40	216/100; 216/101		Noma, Takashi et al.	<input type="checkbox"/>
157	117/8	117/930; 257/E21.012; 257/E21.133; 257/E21.197; 257/E21.352; 257/E21.396; 257/E21.413; 257/E21.414; 257/E21.426; 257/E21.428; 257/E21.43; 257/E29.293; 257/E29.294; 438/166; 438/481; 438/486		Okada, Takako et al.	<input type="checkbox"/>
158	134/2	134/3; 257/E21.226; 257/E21.252; 438/477; 438/906		Sugino, Rinji et al.	<input type="checkbox"/>
159	427/487	427/374.1; 427/379; 427/385.5; 427/58		Ribi, Hans O. et al.	<input type="checkbox"/>
160	264/401	118/423; 118/620; 250/432R; 264/308; 425/174.4; 427/595; 430/270.1		Bae, Young C. et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
161	<input type="checkbox"/>	US 5531857 A	19960702	24	Removal of surface contaminants by irradiation from a high energy source
162	<input type="checkbox"/>	US 5529728 A	19960625	43	Process for lens curing and coating
163	<input type="checkbox"/>	US 5518542 A	19960521	34	Double-sided substrate cleaning apparatus
164	<input type="checkbox"/>	US 5518360 A	19960521	37	Wafer carrying device and wafer carrying method
165	<input type="checkbox"/>	US 5512108 A	19960430	26	Thermophotovoltaic systems
166	<input type="checkbox"/>	US 5491097 A	19960213	20	Analyte detection with multilayered bioelectronic conductivity sensors
167	<input type="checkbox"/>	US 5480627 A	19960102	79	Method for treating substrate for electrophotographic photosensitive member and method for making electrophotographic photosensitive member
168	<input type="checkbox"/>	US 5451642 A	19950919	31	Thermoplastic resin composition and article comprising the same
169	<input type="checkbox"/>	US 5440575 A	19950808	12	Article comprising a semiconductor laser with stable facet coating
170	<input type="checkbox"/>	US 5439577 A	19950808	30	Electrochemical device for generating hydroxyl free radicals and oxidizing chemical substances dissolved in water
171	<input type="checkbox"/>	US 5430303 A	19950704	20	Exposure apparatus
172	<input type="checkbox"/>	US 5419781 A	19950530		Flexible photovoltaic device

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161	156/345.5	134/1; 219/121.6; 219/121.68; 257/E21.226; 257/E21.295; 257/E21.3; 257/E21.304; 257/E21.347; 257/E21.58		Engelsberg, Audrey C. et al.	<input type="checkbox"/>
162	264/1.38	264/1.7; 264/2.6; 427/162		Buazza, Omar M. et al.	<input type="checkbox"/>
163	118/52	118/232; 118/240; 118/244; 118/319; 118/321; 118/323; 118/503; 118/58; 118/642; 118/66; 118/712; 118/72; 118/73; 134/902; 15/77; 15/88.2; 414/936; 414/941		Matsukawa, Hiroyuki et al.	<input type="checkbox"/>
164	414/755	384/12; 414/935; 414/936		Toda, Masayuki et al.	<input type="checkbox"/>
165	136/253			Noreen, Darryl L.	<input type="checkbox"/>
166	436/518	422/82.01; 422/82.02; 422/82.03; 422/82.06; 435/7.1; 435/7.5; 435/7.92; 436/501; 436/527; 436/531; 436/806		Ribi, Hans O. et al.	<input type="checkbox"/>
167	430/127	29/DIG.95; 408/56; 430/128; 82/1.11		Takei, Tetsuya et al.	<input type="checkbox"/>
168	525/179	525/184; 525/421; 525/425		Abe, Hiroomi et al.	<input type="checkbox"/>
169	372/49	257/100; 257/632; 257/79; 257/E21.241; 257/E21.278		Chand, Naresh et al.	<input type="checkbox"/>
170	204/268	204/270; 204/278; 204/284; 204/290.13		Weres, Oleh et al.	<input type="checkbox"/>
171	250/492.2	250/492.22; 250/493.1; 355/30		Matsumoto, Yukako et al.	<input type="checkbox"/>
172	136/244	136/245; 136/256; 136/258; 257/E27.125; 257/E31.042		Hamakawa, Yoshihiro et al.	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pages	Title
173	<input type="checkbox"/>	US 5409777 A	19950425		Laminates of polymer shaving perfluorocyclobutane rings
174	<input type="checkbox"/>	US 5409738 A	19950425		Recording medium
175	<input type="checkbox"/>	US 5403616 A	19950404		Method for forming patterned transparent conducting film
176	<input type="checkbox"/>	US 5370745 A	19941206		Apparatus for performing related operations on workpieces
177	<input type="checkbox"/>	US 5364508 A	19941115		Electrochemical method and device for generating hydroxyl free radicals and oxidizing chemical substances dissolved in water
178	<input type="checkbox"/>	US 5328855 A	19940712		Formation of semiconductor diamond
179	<input type="checkbox"/>	US 5325230 A	19940628		Optical members and blanks of synthetic silica glass and method for their production
180	<input type="checkbox"/>	US 5314780 A	19940524		Method for treating metal substrate for electro-photographic photosensitive member and method for manufacturing electrophotographic photosensitive member
181	<input type="checkbox"/>	US 5273782 A	19931228		Coated parts with film having powder-skeleton structure, and method for forming coating
182	<input type="checkbox"/>	US 5248636 A	19930928		Processing method using both a remotely generated plasma and an in-situ plasma with UV irradiation

	Current OR	Current XR f	Retrieval Classif	Invent r	S
173	428/411.1	428/34.4; 428/357; 428/44; 428/451; 428/461; 428/475.8; 428/483; 428/518; 428/77; 526/242; 526/243; 526/244; 526/245; 526/246; 526/247; 526/252; 526/253		Kennedy, Alvin P. et al.	<input type="checkbox"/>
174	427/502	427/130; 427/131; 427/509; 427/534; 427/553		Matsunuma, Satoshi et al.	<input type="checkbox"/>
175	427/126.3	427/226; 427/259; 427/282; 427/287; 427/553; 427/558; 427/559		Hattori, Akiyoshi et al.	<input type="checkbox"/>
176	118/669	118/319; 118/323; 118/620; 118/681; 118/698; 118/704; 118/706		Litteral, Mary O.	<input type="checkbox"/>
177	205/334	205/688; 205/759; 205/760; 210/748; 210/758; 588/207; 588/215; 588/242		Weres, Oleh et al.	<input type="checkbox"/>
178	438/105	117/929; 257/E21.043; 423/446; 438/795		Kitabatake, Makoto et al.	<input type="checkbox"/>
179	359/350	252/588; 65/399; 65/900		Yamagata, Shigeru et al.	<input type="checkbox"/>
180	430/128	430/127		Takei, Tetsuya et al.	<input type="checkbox"/>
181	427/242	205/80; 427/11; 427/192; 427/195; 427/404; 427/407.1; 427/443.1		Sagawa, Masato et al.	<input type="checkbox"/>
182	438/709	216/63; 216/67; 427/569; 427/573; 427/595; 427/596; 438/711; 438/788; 438/792		Davis, Cecil J. et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
183	<input type="checkbox"/>	US 5246782 A	19930921		Laminates of polymers having perfluorocyclobutane rings and polymers containing perfluorocyclobutane rings
184	<input type="checkbox"/>	US 5240746 A	19930831		System for performing related operations on workpieces
185	<input type="checkbox"/>	US 5234105 A	19930810		Packages for circuit boards for preventing oxidation thereof
186	<input type="checkbox"/>	US 5221561 A	19930622		Process for the photochemical treatment of a material using a flash tube light source
187	<input type="checkbox"/>	US 5217559 A	19930608		Apparatus and method for in-situ deep ultraviolet photon-assisted semiconductor wafer processing
188	<input type="checkbox"/>	US 5215867 A	19930601		Method with gas functionalized plasma developed layer
189	<input type="checkbox"/>	US 5214116 A	19930525		Resin derived from sulfur-containing unsaturated compound and having a high refractive index
190	<input type="checkbox"/>	US 5190364 A	19930302		Optical star coupler and method for manufacturing the same
191	<input type="checkbox"/>	US 5158718 A	19921027		Contact lens casting
192	<input type="checkbox"/>	US 5140272 A	19920818		Method of semiconductor surface measurement and an apparatus for realizing the same

	Current OR	Current XRef	Retrieval Classif	Inventor	S
183	428/421	428/423.3; 428/423.4; 428/423.7; 428/424.2; 428/425.5; 428/425.6; 428/901; 428/934; 438/780		Kennedy, Alvin P. et al.	<input type="checkbox"/>
184	427/510	118/319; 118/322; 29/430; 29/792; 29/830; 427/512; 427/515; 427/96; 427/98		O'Connell Litteral, Mary	<input type="checkbox"/>
185	206/706	206/213.1; 206/524.8; 206/714		Sato, Syoji et al.	<input type="checkbox"/>
186	427/534	427/250; 427/255.31; 427/444; 427/535; 427/553; 427/557; 427/558; 427/574; 427/579; 427/583; 427/584; 427/585; 427/595		Flicstein, Jean et al.	<input type="checkbox"/>
187	156/345.35	118/722; 118/723R; 216/66; 216/67; 257/E21.102; 257/E21.349		Moslehi, Mehrdad M. et al.	<input type="checkbox"/>
188	430/323	216/47; 216/62; 216/67; 430/167; 430/194; 430/197; 430/270.1; 430/298; 430/311; 430/312; 430/313; 430/314; 430/315; 430/324; 430/325; 430/326; 430/327		Stillwagon, Larry E. et al.	<input type="checkbox"/>
189	526/286	351/159; 526/289		Matsuoka, Singo et al.	<input type="checkbox"/>
190	385/24	385/15		Imoto, Katsuyuki et al.	<input type="checkbox"/>
191	264/1.36	264/1.32; 264/1.7; 264/2.3; 264/2.6; 264/2.7; 264/402; 264/489; 264/496; 425/808		Thakrar, Ashok et al.	<input type="checkbox"/>
192	324/662	324/690; 324/754		Nishimatsu, Shigeru et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
193	<input type="checkbox"/>	US 5138973 A	19920818		Wafer processing apparatus having independently controllable energy sources
194	<input type="checkbox"/>	US 5127964 A	19920707		Flexible photovoltaic device
195	<input type="checkbox"/>	US 5099557 A	19920331		Removal of surface contaminants by irradiation from a high-energy source
196	<input type="checkbox"/>	US 5086352 A	19920204		Optical members and blanks or synthetic silica glass and method for their production
197	<input type="checkbox"/>	US 5076204 A	19911231		Apparatus for producing semiconductor device
198	<input type="checkbox"/>	US 5074955 A	19911224	10	Process for the anisotropic etching of a III-V material and application to the surface treatment for epitaxial growth
199	<input type="checkbox"/>	US 5024968 A	19910618		Removal of surface contaminants by irradiation from a high-energy source
200	<input type="checkbox"/>	US 4988533 A	19910129	83	Method for deposition of silicon oxide on a wafer
201	<input type="checkbox"/>	US 4987032 A	19910122		Functional organic thin film and method of manufacture thereof
202	<input type="checkbox"/>	US 4963633 A	19901016		Bisacrylate monomers and polymers exhibiting nonlinear optical response
203	<input type="checkbox"/>	US 4949671 A	19900821		Processing apparatus and method

	Current OR	Current XRef	Retrieval Classif	Invent r	S
193	118/723MP	118/719; 118/723E; 118/723ME; 156/345.35; 156/345.36; 156/345.38; 156/345.5; 216/63; 216/69; 427/569; 427/572; 427/575		Davis, Cecil J. et al.	<input type="checkbox"/>
194	136/256	136/244; 136/258; 257/E31.042		Hamakawa, Yoshihiro et al.	<input type="checkbox"/>
195	29/25.01	250/492.1; 250/492.2; 250/492.3; 257/E21.226; 257/E21.295; 257/E21.3; 257/E21.304; 257/E21.347; 257/E21.58		Engelsberg, Audrey C.	<input type="checkbox"/>
196	359/350	252/588; 65/399; 65/900		Yamagata, Shigeru et al.	<input type="checkbox"/>
197	118/719	118/50.1; 118/722; 118/725		Hisamune, Yoshiaki	<input type="checkbox"/>
198	438/504	257/E21.222; 438/44; 438/712; 438/718		Henry, Loic et al.	<input type="checkbox"/>
199	438/597	134/1; 134/1.3; 148/DIG.17; 148/DIG.91; 148/DIG.93; 257/E21.226; 257/E21.295; 257/E21.3; 257/E21.304; 257/E21.347; 257/E21.58; 438/663; 438/906		Engelsberg, Audrey C.	<input type="checkbox"/>
200	427/563	427/294; 427/572; 427/574		Freeman, Dean W. et al.	<input type="checkbox"/>
201	428/411.1	204/157.6; 427/2.13; 427/402; 427/555; 428/420; 428/442; 428/459; 428/500		Miyasaka, Tsutomu et al.	<input type="checkbox"/>
202	526/323.2	252/299.01; 526/245; 526/298; 526/311; 526/312; 526/323.1; 526/326; 560/221		DeMartino, Ronald N. et al.	<input type="checkbox"/>
203	118/725	118/715		Davis, Cecil J. et al.	<input type="checkbox"/>

	1	Document ID	Issue Dat	Pages	Title
204	<input type="checkbox"/>	US 4931279 A	19900605		Sustained release formulation containing an ion-exchange resin
205	<input type="checkbox"/>	US 4931125 A	19900605		Method for adhesive bonding with pretreatment of components
206	<input type="checkbox"/>	US 4929696 A	19900529		Bisacrylate monomers and polymers exhibiting nonlinear optical response
207	<input type="checkbox"/>	US 4923948 A	19900508		Curable composition
208	<input type="checkbox"/>	US 4923562 A	19900508		Processing of etching refractory metals
209	<input type="checkbox"/>	US 4922003 A	19900501		Bisacrylate monomers and polymers exhibiting nonlinear optical response
210	<input type="checkbox"/>	US 4921321 A	19900501		Silicon network polymers
211	<input type="checkbox"/>	US 4917123 A	19900417		Apparatus for treating wafers with process fluids
212	<input type="checkbox"/>	US 4915777 A	19900410		Method for etching tungsten
213	<input type="checkbox"/>	US 4911103 A	19900327		Processing apparatus and method
214	<input type="checkbox"/>	US 4910043 A	19900320		Processing apparatus and method
215	<input type="checkbox"/>	US 4908292 A	19900313		Method of making an electrophotographic inorganic photosensitive element using ultraviolet radiation
216	<input type="checkbox"/>	US 4906328 A	19900306		Method for wafer treating
217	<input type="checkbox"/>	US 4904621 A	19900227		Remote plasma generation process using a two-stage showerhead

	Current OR	Current XRef	Retrieval Classif	Inventor	S
204	424/427	424/429; 424/487; 424/78.04; 523/106; 525/326.1; 525/326.3; 525/326.6; 525/329.7; 525/330.3; 525/332.2; 525/333.3		Bawa, Rajan et al.	<input type="checkbox"/>
205	156/272.8	156/273.3; 156/275.7; 156/309.9; 216/58; 216/65; 219/121.64; 219/121.66; 427/516		Volkman, Curtis L. et al.	<input type="checkbox"/>
206	526/312	560/221		DeMartino, Ronald N. et al.	<input type="checkbox"/>
207	528/26	525/431		Matsuki, Yasuo et al.	<input type="checkbox"/>
208	216/67	204/192.35; 216/75; 257/E21.311		Jucha, Rhett B. et al.	<input type="checkbox"/>
209	560/221	526/312		DeMartino, Ronald N. et al.	<input type="checkbox"/>
210	385/130	257/E21.301; 385/14; 385/141; 528/33		Weidman, Timothy W.	<input type="checkbox"/>
211	134/95.2	134/100.1; 134/103.2; 134/902; 134/98.1; 210/167; 210/411		McConnell, Christopher F. et al.	<input type="checkbox"/>
212	438/711	252/79.1; 257/E21.311; 438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
213	118/725	118/715; 118/728; 118/729; 156/345.51; 250/441.11		Davis, Cecil J. et al.	<input type="checkbox"/>
214	427/563	118/722; 118/723ME; 257/E21.311; 427/572; 438/792		Freeman, Dean W. et al.	<input type="checkbox"/>
215	430/128	430/130; 430/135		Ide, Yukio et al.	<input type="checkbox"/>
216	438/694	427/299; 427/399; 427/554; 427/557; 438/703; 438/770; 438/906		Freeman, Dean W. et al.	<input type="checkbox"/>
217	134/1.2	118/50.1; 118/620; 118/728; 257/E21.256; 427/562; 438/719; 438/731		Loewenstein, Lee M. et al.	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pag s	Title
218	<input type="checkbox"/>	US 4900695 A	19900213		Semiconductor integrated circuit device and process for producing the same
219	<input type="checkbox"/>	US 4892402 A	19900109		Method for making contact lens hydrophilic
220	<input type="checkbox"/>	US 4891488 A	19900102		Processing apparatus and method
221	<input type="checkbox"/>	US 4886570 A	19891212		Processing apparatus and method
222	<input type="checkbox"/>	US 4877757 A	19891031		Method of sequential cleaning and passivating a GaAs substrate using remote oxygen plasma
223	<input type="checkbox"/>	US 4875989 A	19891024		Wafer processing apparatus
224	<input type="checkbox"/>	US 4875943 A	19891024		Flexible photovoltaic device
225	<input type="checkbox"/>	US 4874723 A	19891017		Selective etching of tungsten by remote and in situ plasma generation
226	<input type="checkbox"/>	US 4874634 A	19891017		Vapor phase deposition of cadmium and mercury telluride for electronic device manufacture
227	<input type="checkbox"/>	US 4872938 A	19891010		Processing apparatus
228	<input type="checkbox"/>	US 4867841 A	19890919		Method for etch of polysilicon film
229	<input type="checkbox"/>	US 4863558 A	19890905		Method for etching tungsten
230	<input type="checkbox"/>	US 4863557 A	19890905		Pattern forming process and thin-film magnetic head formed by said process

	Current OR	Current XR f	Retri val Classif	Inventor	S
218	438/625	250/492.2; 257/750; 257/774; 257/E21.575; 257/E21.586; 257/E21.592; 257/E21.596; 257/E23.148; 438/635; 438/637; 438/641; 438/676; 438/940		Takahashi, Takahiko et al.	<input type="checkbox"/>
219	351/160H	427/162; 427/164; 427/519		Sawamoto, Takeyuki et al.	<input type="checkbox"/>
220	219/121.4	118/709; 156/345.43; 204/298.09; 204/298.25; 219/121.42; 219/121.43		Davis, Cecil J. et al.	<input type="checkbox"/>
221	438/711	118/50.1; 156/345.35; 156/345.37; 156/345.38; 156/345.5		Davis, Cecil J. et al.	<input type="checkbox"/>
222	438/767	134/1.2; 148/DIG.17; 148/DIG.21; 148/DIG.56; 216/67; 257/E21.485; 257/E21.493; 427/534; 427/562; 427/582; 438/694		York, Rudy L. et al.	<input type="checkbox"/>
223	204/298.33	156/345.33; 156/345.37; 204/192.1		Davis, Cecil J. et al.	<input type="checkbox"/>
224	136/244	136/256; 136/258; 257/E31.042		Hamakawa, Yoshihiro et al.	<input type="checkbox"/>
225	438/696	118/620; 148/DIG.51; 204/192.1; 204/298.35; 216/71; 216/75; 257/E21.311; 438/711; 438/720; 438/730; 438/963		Jucha, Rhett B. et al.	<input type="checkbox"/>
226	427/584	427/255.33; 427/255.7		Easton, Brian C. et al.	<input type="checkbox"/>
227	156/345.54	118/729		Davis, Cecil J. et al.	<input type="checkbox"/>
228	438/711	257/E21.312; 438/719		Loewenstein, Lee M. et al.	<input type="checkbox"/>
229	438/695	438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
230	216/22	204/192.32; 216/47; 216/48; 216/67; 216/77; 216/79; 216/81; 360/122; 427/130; 427/131; 427/488; 428/694R		Kokaku, Yuuichi et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
231	<input type="checkbox"/>	US 4857132 A	19890815		Processing apparatus for wafers
232	<input type="checkbox"/>	US 4855160 A	19890808		Method for passivating wafer
233	<input type="checkbox"/>	US 4855016 A	19890808		Method for etching aluminum film doped with copper
234	<input type="checkbox"/>	US 4849067 A	19890718		Method for etching tungsten
235	<input type="checkbox"/>	US 4844773 A	19890704		Process for etching silicon nitride film
236	<input type="checkbox"/>	US 4842687 A	19890627		Method for etching tungsten
237	<input type="checkbox"/>	US 4842686 A	19890627		Wafer processing apparatus and method
238	<input type="checkbox"/>	US 4842676 A	19890627		Process for etch of tungsten
239	<input type="checkbox"/>	US 4838990 A	19890613		Method for plasma etching tungsten
240	<input type="checkbox"/>	US 4838984 A	19890613		Method for etching films of mercury-cadmium-telluride and zinc sulfid
241	<input type="checkbox"/>	US 4837113 A	19890606		Method for depositing compound from group II-VI
242	<input type="checkbox"/>	US 4836905 A	19890606		Processing apparatus
243	<input type="checkbox"/>	US 4832779 A	19890523		Processing apparatus
244	<input type="checkbox"/>	US 4832778 A	19890523		Processing apparatus for wafers
245	<input type="checkbox"/>	US 4832777 A	19890523		Processing apparatus and method
246	<input type="checkbox"/>	US 4830705 A	19890516		Method for etch of GaAs
247	<input type="checkbox"/>	US 4830700 A	19890516		Processing apparatus and method
248	<input type="checkbox"/>	US 4828649 A	19890509		Method for etching an aluminum film doped with silicon
249	<input type="checkbox"/>	US 4822450 A	19890418		Processing apparatus and method
250	<input type="checkbox"/>	US 4820378 A	19890411		Process for etching silicon nitride selectively to silicon oxide

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231	156/345.33	118/50.1; 438/935		Fisher, Wayne G.	<input type="checkbox"/>
232	438/767	204/192.1; 257/E21.493; 257/E21.494; 427/553; 427/585		Luttmer, Joseph D. et al.	<input type="checkbox"/>
233	438/710	257/E21.311; 438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
234	216/75	257/E21.311		Jucha, Rhett B. et al.	<input type="checkbox"/>
235	438/711	257/E21.252; 438/719; 438/727		Loewenstein, Lee M. et al.	<input type="checkbox"/>
236	438/711	252/79.1; 257/E21.234; 257/E21.311; 438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
237	438/709	156/345.37; 156/345.38; 156/345.5		Davis, Cecil J. et al.	<input type="checkbox"/>
238	438/711	216/75; 257/E21.311; 438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
239	438/711	204/192.35; 216/75; 252/79.1; 257/E21.311; 438/720		Jucha, Rhett B. et al.	<input type="checkbox"/>
240	438/711	257/E21.485; 438/718		Luttmer, Joseph D. et al.	<input type="checkbox"/>
241	117/103	117/104; 427/562; 427/572; 438/935		Luttmer, Joseph D. et al.	<input type="checkbox"/>
242	204/298.25	118/719; 156/345.51; 204/192.12; 414/936; 414/937		Davis, Cecil J. et al.	<input type="checkbox"/>
243	156/345.37	216/100; 216/102; 216/13		Fisher, Wayne G. et al.	<input type="checkbox"/>
244	156/345.31	118/50.1; 118/620; 118/728		Davis, Cecil J. et al.	<input type="checkbox"/>
245	156/345.37	118/725; 438/715		Davis, Cecil J. et al.	<input type="checkbox"/>
246	438/718	204/192.35; 252/79.1; 257/E21.222		Loewenstein, Lee M. et al.	<input type="checkbox"/>
247	156/345.37	216/21; 216/41; 216/67		Davis, Cecil J. et al.	<input type="checkbox"/>
248	438/711	204/192.37; 216/77; 257/E21.311; 438/720		Davis, Cecil J. et al.	<input type="checkbox"/>
249	438/709	156/345.35; 156/345.36; 156/345.37; 156/345.38; 156/345.5; 438/730		Davis, Cecil J. et al.	<input type="checkbox"/>
250	438/711	204/192.37; 257/E21.252; 438/724; 438/738; 438/744		Loewenstein, Lee M.	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pages	Title
251	<input type="checkbox"/>	US 4820377 A	19890411		Method for cleanup processing chamber and vacuum process module
252	<input type="checkbox"/>	US 4818327 A	19890404		Wafer processing apparatus
253	<input type="checkbox"/>	US 4818326 A	19890404		Processing apparatus
254	<input type="checkbox"/>	US 4816098 A	19890328		Apparatus for transferring workpieces
255	<input type="checkbox"/>	US 4801352 A	19890131		Flowing gas seal enclosure for processing workpiece surface with controlled gas environment and intense laser irradiation
256	<input type="checkbox"/>	US 4778532 A	19881018		Process and apparatus for treating wafers with process fluids
257	<input type="checkbox"/>	US 4773942 A	19880927		Flexible photovoltaic device
258	<input type="checkbox"/>	US 4711790 A	19871208		Optical CVD method with a strong optical intensity used during an initial period and device therefor
259	<input type="checkbox"/>	US 4668506 A	19870526		Sustained-release formulation containing and amino acid polymer
260	<input type="checkbox"/>	US 4612409 A	19860916		Flexible photovoltaic device
261	<input type="checkbox"/>	US 4586996 A	19860506		Surface hardner for nylon lens
262	<input type="checkbox"/>	US 4526920 A	19850702		Curable coating composition containing acryloyl or methacryloyl cyanurate or isocyanurate compound, cured composition therefrom, and process for producing articles by using the curable composition
263	<input type="checkbox"/>	US 4515804 A	19850507		Crystal modifications of (+)-catechin and pharmaceutical preparations containing them

	Current OR	Current XRef	Retri val Classif	Inventor	S
251	134/1.1	134/1; 156/345.35; 156/345.37; 156/345.38; 438/715; 438/905		Davis, Cecil J. et al.	<input type="checkbox"/>
252	156/345.37	118/620; 204/298.09; 438/715		Davis, Cecil J. et al.	<input type="checkbox"/>
253	156/345.36	156/345.39; 156/345.53; 204/298.25; 204/298.35; 313/361.1		Liu, Jiann et al.	<input type="checkbox"/>
254	156/345.31	118/728; 204/298.25; 414/939; 438/716		Davis, Cecil J. et al.	<input type="checkbox"/>
255	156/345.5	118/50.1; 118/620; 118/640; 118/729; 219/121.61; 219/121.69; 219/121.84; 219/121.85; 427/248.1		Piwczyk, Bernhard	<input type="checkbox"/>
256	134/10	134/18; 134/25.1; 134/25.4; 134/26; 134/28; 134/29; 134/30; 134/31; 210/739; 417/122		McConnell, Christopher F. et al.	<input type="checkbox"/>
257	136/244	136/256; 136/258; 257/E31.042		Hamakawa, Yoshihiro et al.	<input type="checkbox"/>
258	427/10	118/50.1; 118/620; 118/666; 427/586		Morishige, Yukio	<input type="checkbox"/>
259	424/429	351/160H; 351/160R; 351/177; 424/427; 424/449; 424/486; 514/912; 514/913; 514/954; 523/106; 523/107; 523/108		Bawa, Rajan	<input type="checkbox"/>
260	136/244	136/256; 136/258; 257/E31.042		Hamakawa, Yoshihiro et al.	<input type="checkbox"/>
261	522/7	351/166; 428/447; 428/475.5		Shinohara, Kazuhiro et al.	<input type="checkbox"/>
262	522/78	522/166; 522/167; 522/42; 522/79; 522/83; 524/548; 524/850; 526/261		Sakashita, Takeshi et al.	<input type="checkbox"/>
263	514/456	514/894; 549/399		Marti, Erwin et al.	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pages	Title
264	<input type="checkbox"/>	US 4503126 A	19850305		Method of making an abrasion resistant coating on a solid substrate and articles produced thereby
265	<input type="checkbox"/>	US 4444618 A	19840424		Processes and gas mixtures for the reactive ion etching of aluminum and aluminum alloys
266	<input type="checkbox"/>	US 4436764 A	19840313		Method and apparatus for surface-hardening treatment of synthetic resin shaped articles
267	<input type="checkbox"/>	US 4435476 A	19840306		Method of making an abrasion resistant coating on a solid substrate and articles produced thereby
268	<input type="checkbox"/>	US 4427823 A	19840124		Cured or uncured filled coating composition of polyfunctional acrylic-type acid ester and utilization thereof
269	<input type="checkbox"/>	US 4388428 A	19830614		Biologically stabilized compositions comprising collagen as the major component with ethylenically unsaturated compounds used as contact lenses
270	<input type="checkbox"/>	US 4351881 A	19820928		Radiation cured acrylate coating method and coated product
271	<input type="checkbox"/>	US 4345000 A	19820817		Transparent electrically conductive film
272	<input type="checkbox"/>	US 4278754 A	19810714		Resists and method of manufacturing semiconductor elements by using the same

	Current OR	Current XRef	Retrieval Classif	Inventor	S
264	428/412	427/503; 428/447; 428/450; 428/474.4; 428/480; 428/522; 428/532		Phillips, Richard A. et al.	<input type="checkbox"/>
265	438/669	204/192.32; 216/77; 252/79.1; 257/E21.313; 438/712; 438/720		Saia, Richard J. et al.	<input type="checkbox"/>
266	427/512	118/423; 118/428; 118/620; 427/430.1		Nakazima, Atushi et al.	<input type="checkbox"/>
267	428/412	427/525; 427/536; 428/447; 428/450; 428/474.4; 428/480; 428/522		Phillips, Richard A. et al.	<input type="checkbox"/>
268	522/83	522/168; 522/171; 524/531; 524/833; 524/851; 524/854		Inagaki, Hajime et al.	<input type="checkbox"/>
269	523/106	351/160H; 523/108; 523/449; 524/21; 524/23; 524/704; 525/937		Kuzma, Petr et al.	<input type="checkbox"/>
270	428/412	427/520; 428/522; 526/277		Kamada, Kazumasa et al.	<input type="checkbox"/>
271	428/212	427/109; 427/124; 427/126.3; 428/218; 428/336; 428/457; 428/458; 428/697; 428/701; 428/938		Kawazoe, Shozo et al.	<input type="checkbox"/>
272	430/323	430/280.1; 430/281.1; 430/296; 430/297; 430/313; 430/317; 430/318; 430/326; 430/328; 430/330; 430/942		Yamashita, Yoshio et al.	<input type="checkbox"/>

	1	Document ID	Issue Date	Pages	Title
273	<input type="checkbox"/>	US 4274933 A	19810623		Coating composition
274	<input type="checkbox"/>	US 4084021 A	19780411		Method for rendering substrates resistant to abrasion
275	<input type="checkbox"/>	US 4073967 A	19780214		Method for rendering substrates resistant to abrasion
276	<input type="checkbox"/>	US 4067839 A	19780110		Hydrophilic copolymer of N,N-(C.sub.1 -C.sub.2 alkyl) acrylamide
277	<input type="checkbox"/>	US 4042749 A	19770816		Article having abrasion resistant surface formed from the reaction product of a silane and a metal ester
278	<input type="checkbox"/>	US 4028080 A	19770607	3	Method of treating optical waveguide fibers
279	<input type="checkbox"/>	US 3978178 A	19760831		Process for producing abrasion-resistant cast article
280	<input type="checkbox"/>	US 3973022 A	19760803		Quinolineacetic acid compositions
281	<input type="checkbox"/>	US 3926964 A	19751216		New oxazole compounds, process for their manufacture, and their use as optical brighteners for organic materials

	Current OR	Current XRef	Retrieval Classif	Inventor	S
273	522/171	252/600; 264/1.1; 264/447; 264/485; 264/488; 351/166; 427/164; 427/389.7; 524/547; 524/807; 526/222; 526/227; 526/232; 526/277; 526/278; 526/302; 526/329.7		Kamada, Kazumasa et al.	<input type="checkbox"/>
274	427/493	427/164; 427/165; 427/386; 427/387; 427/503; 427/515		Sandvig, Timothy C.	<input type="checkbox"/>
275	427/503	106/287.13; 427/299; 427/307; 427/322; 427/372.2; 427/388.1; 427/389.7; 427/393.5; 427/515; 428/412; 428/422; 428/429; 428/447; 428/522; 522/172; 526/279; 528/17; 528/25; 528/395; 556/438		Sandvig, Timothy C.	<input type="checkbox"/>
276	523/108	264/2.6; 351/160R; 524/555; 524/916; 526/916		Schultz, Herman S.	<input type="checkbox"/>
277	428/412	427/503; 427/515; 428/447; 428/457; 528/29		Sandvig, Timothy C.	<input type="checkbox"/>
278	65/425	134/1; 134/2; 250/504R; 385/123; 65/432		Di Vita, Sam et al.	<input type="checkbox"/>
279	264/488	264/166; 264/236; 264/255; 264/331.18; 264/338; 264/347; 264/495		Oshima, Akira et al.	<input type="checkbox"/>
280	514/311	514/314; 514/825		Goschke, Richard	<input type="checkbox"/>
281	548/224	162/162; 252/301.24; 510/307; 987/65		Liechti, Peter	<input type="checkbox"/>

	1	D cument ID	Issue Date	Pages	Titl
282	<input type="checkbox"/>	US 3901883 A	19750826		Azole compounds
283	<input type="checkbox"/>	US 3887813 A	19750603		Short wavelength fluorescent light source
284	<input type="checkbox"/>	US 3871885 A	19750318		CRYSTALLINE PHOTO-POLYMERIZABLE COMPOSITION
285	<input type="checkbox"/>	US 3857054 A	19741224		DISCHARGE DEVICE AND METHOD FOR GENERATING NEAR INFRARED RADIATIONS
286	<input type="checkbox"/>	US 3736427 A	19730529		SHORT WAVELENGTH FLUORESCENT LIGHT SOURCE

	Current OR	Current XRef	Retri val Classif	Inventor	S
282	548/217	106/150.1; 106/170.1; 106/170.11; 106/173.01; 106/200.2; 252/301.22; 252/301.24; 427/158; 430/572; 430/77; 430/78; 430/933; 548/113; 548/218; 548/224; 548/255; 548/302.1; 548/310.7; 562/475; 562/492; 564/134; 564/139; 564/142; 564/161; 987/154; 987/65		Liechti, Peter et al.	<input type="checkbox"/>
283	250/461.1	250/504R; 313/489		Allington, Robert W.	<input type="checkbox"/>
284	430/281.1	430/271.1; 430/283.1; 430/916; 430/923; 522/37; 522/39; 522/40; 522/43; 522/46; 522/6; 522/63; 522/9		Hertler, Walter Raymond	<input type="checkbox"/>
285	313/486	250/504R; 252/301.4R; 52/309.17		Lehmann, Willi et al.	<input type="checkbox"/>
286	250/461.1	250/504R; 313/489		Allington, Robert W.	<input type="checkbox"/>